#2/A 9.2 4/30/02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

T. HASHIMOTO et al

Serial No.

Filed: March 4, 2002

For: A SEMICONDUCTOR DEVICE AND A METHOD OF

MANUFACTURING THE SAME

PRELIMINARY AMENDMENT

Commissioner for Patents Washington, D.C. 20231

Sir:

Prior to the examination thereof, please amend the aboveidentified application as follows.

IN THE CLAIMS

/ Please rewrite claim 14 as set forth below.



14. (Amended) The semiconductor device according to claim 11, wherein the epitaxial layer is comprised mainly of silicon-germanium, silicon-germanium-carbon, or silicon.